Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	10913	(polymer$3 organic) with mask	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/05 14:25
L3	2034	2 and ((Squeeze Stretch$3 Reposition$3 position$3) with mask)	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/05 14:25
L5	1836	3 and ((form$3 depoist$3 implant$3 dop$3) with mask)	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/05 14:25
L6	1568	5 and (substrate wafer semiconductor)	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/05 14:26
L7	5360	(polymer$3 organic) with mask	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 14:25
L8	394	7 and ((Squeeze Stretch$3 Reposition$3 position$3) and mask)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 14:25
L9	293	8 and ((form$3 depoist$3 implant$3 dop$3) and mask)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 14:26
L10	190	9 and (substrate wafer semiconductor)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 14:26
L11	190	10 and (substrate wafer semiconductor)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 14:26